

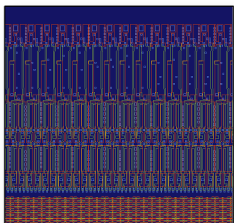
EQUICON

ePLACE

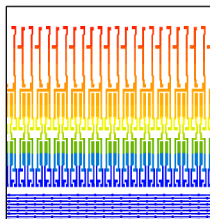
- Data Manipulation
- Fracturing
- Proximity Correction
- Simulation
- Visualization

e-Beam Data Preparation Software

Easy Workflow



Visualization of layout
before processing



After data manipulation & proximity
correction (colors are doses)



ePLACE
Client



sends tasks and
complex procedures



visualizes progress
and processing results



from design



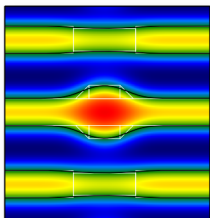
ePLACE Server
(compute cluster)

to exposure

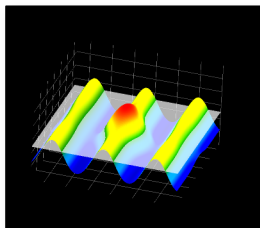


Exposure Data

Design Data



Simulated e-beam dose deposition and resist contour



3D visualization of e-beam dose deposition

ePLACE is suitable for all fields of application in e-beam lithography in academic and industrial research, high-end mask and direct write production lines and in the production of micro-optical and micro-mechanical elements. ePLACE combines a user-friendly GUI with proven kernels for layout processing and simulation. The client-server architecture enables a scalability range of one up to hundreds of CPUs. The flexible workflow allows procedures that process the design data and automatically send the exposure data to the exposure tool – all with one click of the mouse. Special modules and algorithms for proximity correction, and resolution and contrast enhancement are available.

Key Features

Characteristics & Functions

- User-friendly GUI
- Flexible Workflow definition
- Common Boolean operations (AND, OR, XOR, NEG)
- Geometric transformations (translation, rotation, scaling, sizing, overlap removal and others)
- PROXECCO Proximity effect correction with Geometrical Induced Dose Correction (GIDC) contrast enhancement technology (see also PROXECCO and GIDC brochure)
- Field proven fracture quality, special attention on sliver issues
- Shot count optimization for minimal writing time
- Comprehensive visualization capabilities (layout data, intermediate results, fracture data, e-beam shots/ runtime format)
- Controlled data transfer to exposure equipment
- Exposure simulation
- Full support for Vistec e-beam writers (including cell projection writers)
- Scalable distributed high performance computing

Supported File Formats

- OASIS
- GDSII
- DXF
- CIF
- BMP (Bitmap)
- ZBA 2x
- ZBA 3x
- JES (Vistec SB tools)
- OASIS.MASK
- Others on request

Any of the above listed options may be licensed to customers.

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